

## VUV Photocatalytic Degradation of Toluene in the Gas Phase

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The photocatalytic degradation rate of gaseous toluene under irradiation of vacuum ultraviolet (185 nm) was 2–3 times faster than that under irradiation of 254 nm. The 185-nm VUV photolysis was greatly improved by the presence of TiO<sub>2</sub> photocatalyst.

The heterogeneous photocatalysis is considered as one of the most promising methods to decontaminate indoor pollutants such as volatile organic compounds (VOCs), bacteria, and allergen. Photocatalytic degradations of various kinds of VOCs and bacteria in the gas phase have been widely investigated in the past two decades.<sup>1–3</sup> And the commercial air purifiers based on photocatalysis have been on sale. However the deactivation of TiO<sub>2</sub> photocatalyst during VOCs degradation was reported frequently.<sup>4,5</sup> The main reason was the accumulation of intermediate on the surfaces of the photocatalyst because of its slow reaction rate. The combination of photocatalysis with microwave,<sup>6</sup> magnetic field,<sup>7</sup> or ozone<sup>8</sup> was investigated to enhance photocatalysis, which accordingly resulted in extra cost.

Vacuum ultraviolet (VUV) with high-energy photon (185 nm wavelength corresponds to a photon energy 6.7 eV) can break most chemical bonds. Under VUV irradiation, oxygen and water in air are dissociated and accordingly ozone and hydroxyl radical are formed. In the meanwhile, VOCs may also be photolyzed by VUV directly. Though low-pressure mercury lamp emitting 185-nm VUV was evaluated to generate ozone long before,<sup>9</sup> its feasibility for air purification was little investigated probably because of low radiation at 185 nm. We found that toluene, a typical indoor VOC, was effectively degraded by 185-nm VUV, furthermore the presence of TiO<sub>2</sub> greatly increased the degradation rate of toluene by VUV.

Photochemical reactions were conducted in a cylindrical reactor with diameter of 64 mm, length of 530 mm and effective volume 1.44 L, reported elsewhere.<sup>8</sup> A 15-W low-pressure mercury lamp emitting 254 and 185 nm was placed at the center of the reactor, ozone generated by this lamp depended on flow rate and humidity as shown in Figure 1. The same power lamp only emitting 254 nm was used for UV photocatalysis. The TiO<sub>2</sub> coated aluminum sheet (440 mm × 201 mm) was closely attached the interior surface of the reactor. The diluted toluene gas was continuously generated by blowing toluene in a saturator and detected with GC/FID.

Figure 2 clearly shows that toluene was degraded fastest by VUV photocatalysis (TiO<sub>2</sub>/VUV) among three processes. The reaction rate by TiO<sub>2</sub>/VUV continuously increased with increase of inlet concentration of toluene, which was in good agreement with Langmuir–Hinshelwood (L–H) model as shown in Figure 3 ( $k = 51.8 \text{ mg/m}^3 \cdot \text{min}$ ,  $K = 0.49 \text{ m}^3/\text{mg}$ ). On the contrary, the reaction rate reached a maximum in the VUV and TiO<sub>2</sub>/UV (254 nm) processes and did not agree with L–H model. The reaction rate of TiO<sub>2</sub>/VUV at inlet concentration

$7 \text{ mg/m}^3$  was more than  $20 \text{ mg/m}^3 \cdot \text{min}$ , however it was only  $10 \text{ mg/m}^3 \cdot \text{min}$  or less for other two processes.

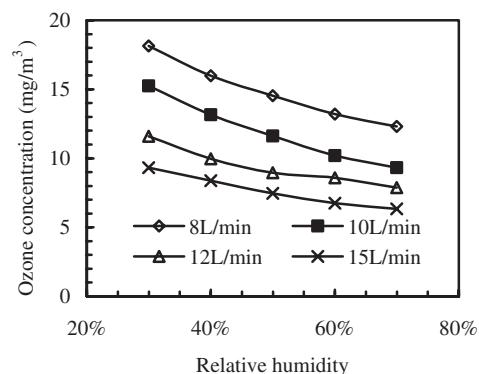


Figure 1. Ozone production by the VUV lamp.

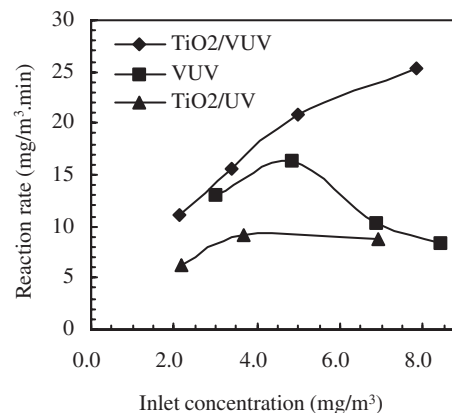
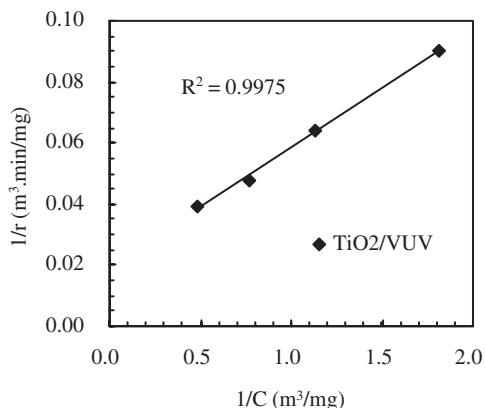


Figure 2. Variation of reaction rate with toluene concentration ( $Q = 12 \text{ L/min}$ ,  $\text{RH} = 35\%$ ).

In the VUV/TiO<sub>2</sub> process, toluene was degraded via multiple pathways: (1) direct photolysis resulting from 185-nm VUV absorption by toluene; (2) reactions with reactive species like atom oxygen and hydroxyl radical generated from water and oxygen dissociation by 185nm ( $\text{H}_2\text{O} + 185 \text{ nm} \rightarrow \text{H} + \text{OH}$ ,  $\text{O}_2 + 185 \text{ nm} \rightarrow 2 \text{ O}$ ,  $\text{O} + \text{H}_2\text{O} \rightarrow 2 \text{ OH}$ ); (3) photocatalysis on the TiO<sub>2</sub> surface by 254 and 185 nm. Accordingly toluene degraded fastest in VUV/TiO<sub>2</sub> process. It was still not clear why in the VUV process the reaction rate decreased at higher toluene concentration. One possible reason was the competitive absorption of 185-nm light by toluene ( $\epsilon$  at 185 nm is about  $9000 \text{ cm}^{-1} \text{ M}^{-1}$ ),<sup>10</sup> which consequently reduced the hydroxyl radical formation from water and oxygen dissociation.

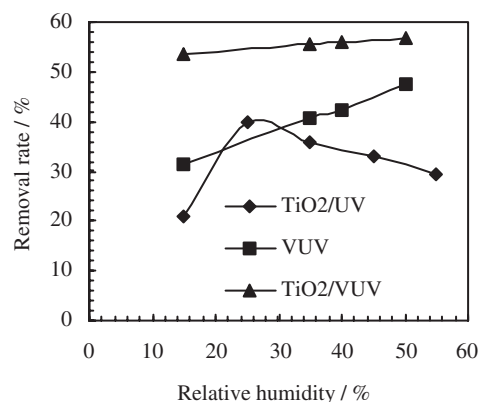
Figure 4 shows the effect of relative humidity (RH) on the removal rate of toluene. VUV and TiO<sub>2</sub>/UV were more signifi-



**Figure 3.** Plot of reciprocal of reaction rate ( $1/r$ ) vs the reciprocal of toluene concentration ( $1/C$ ).

cantly influenced than the  $\text{TiO}_2/\text{VUV}$ . It has been well demonstrated that in the  $\text{TiO}_2/\text{UV}$  process reaction rate firstly increased with RH increase and then decreased due to competition adsorption of water molecules with VOC on the  $\text{TiO}_2$  surface.<sup>11</sup> The competitive adsorption of water reduced the reaction rate of toluene on  $\text{TiO}_2$  surface. For VUV photolysis, though with RH increase less ozone was generated as shown in Figure 1, the removal rate of toluene increased greatly. It is understandable that with increase of humidity, more 185-nm photons were absorbed by water molecule and accordingly more hydroxyl radicals were generated, by which toluene degraded more effectively, and less photon was absorbed by oxygen molecule resulting in reduced ozone generation. In addition, more hydroxyl radicals were generated via reaction between water and atom oxygen resulting from oxygen dissociation by 185-nm light, while the ozone generation was reduced ( $\text{O} + \text{O}_2 \rightarrow \text{O}_3$ ). For the  $\text{TiO}_2/\text{VUV}$  process, the removal rate increased more slowly than in VUV process with RH increase due to water competitive adsorption with toluene on  $\text{TiO}_2$  surface.

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**Figure 4.** The effect of relative humidity on removal rate ( $C_0 = 3.5\text{--}5.2 \text{ mg/m}^3$ ,  $Q = 12 \text{ L/min}$ ).

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